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# Fabrication of Er-doped Microresonator for On-chip Mode-locked Laser with CNT as Saturable Absorber

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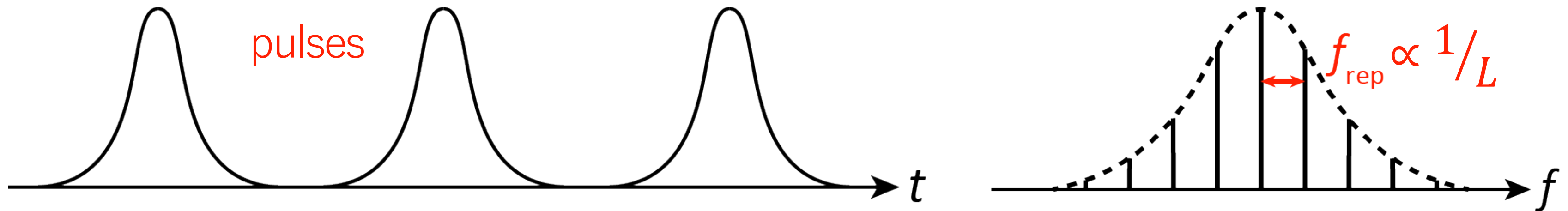


# Outline

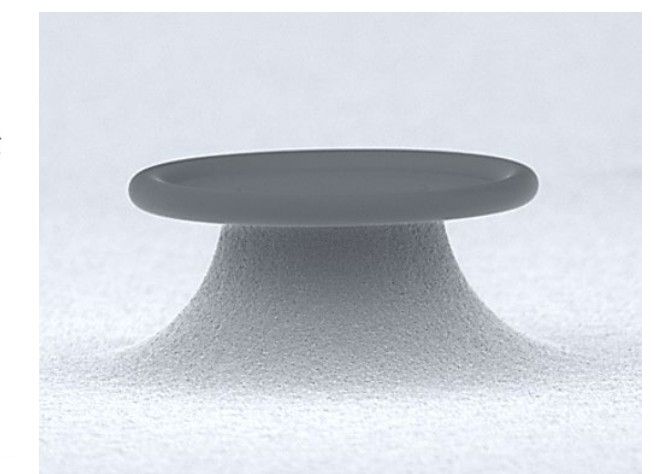
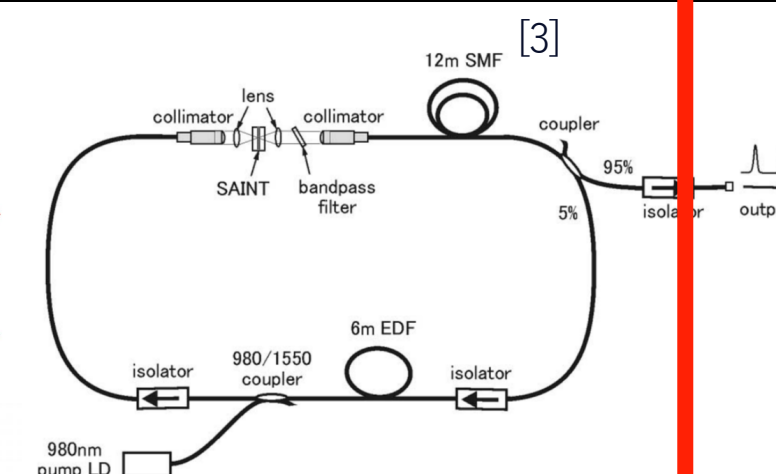
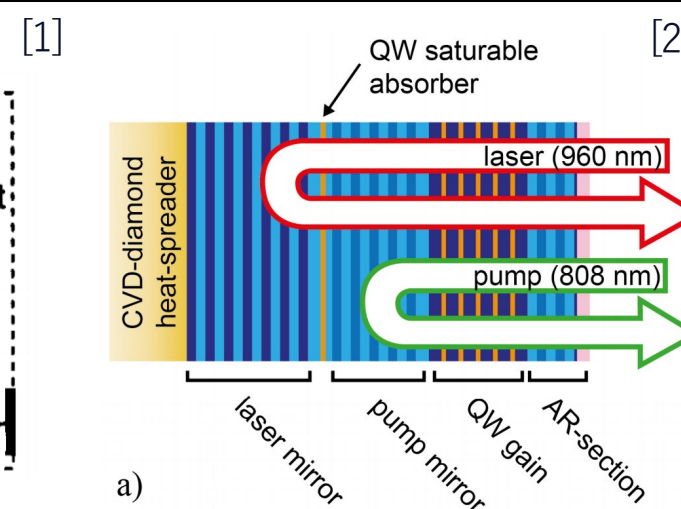
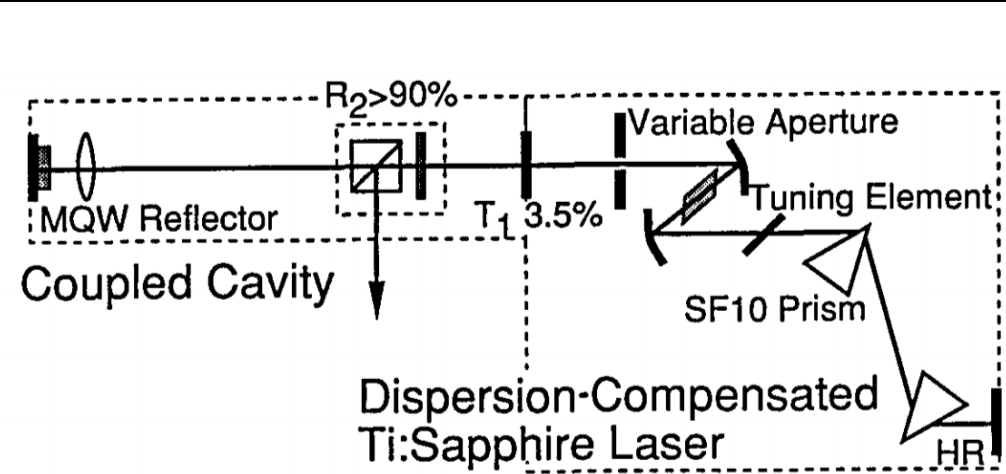
- Background & Objective
- Saturable absorption of CNT
- Er-doped microresonator
- Summary



# Background: mode-locked laser



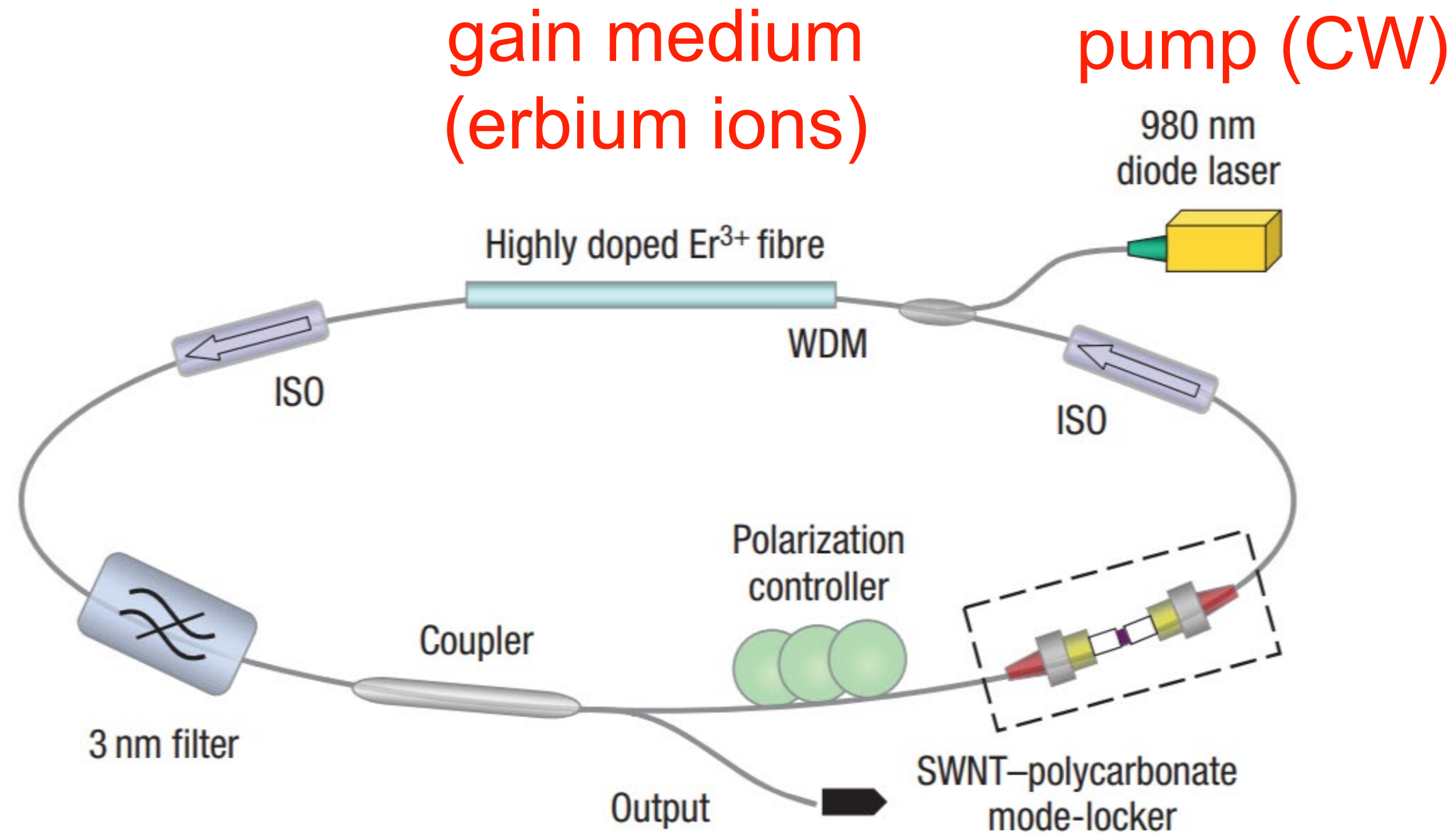
laser type	solid-state	semiconductor (MIXSEL)	fiber	microcavity
pulse width	~ 100 fs	~ 1 ps	~ 1 ps	~ 100 fs
repetition rate	~ 100 MHz	~ 10 GHz	~ 200 MHz	< 1000 GHz
wavelength	850 nm	650 ~ 2200 nm	1550 nm	1550 nm
integration	×	○	△	◎



[1] U. Keller, *et al.*, Opt. Lett., **16**, 13, 1022-1024 (1991) [2] M. Mangold, *et al.*, Opt. Express **22**, 6099-6107 (2014) [3] Sze Y. Set, IEEE J. Sel. Top. Quantum Electron., **10**, 1, 137-146 (2004)



# Background: mode-locked fiber ring system



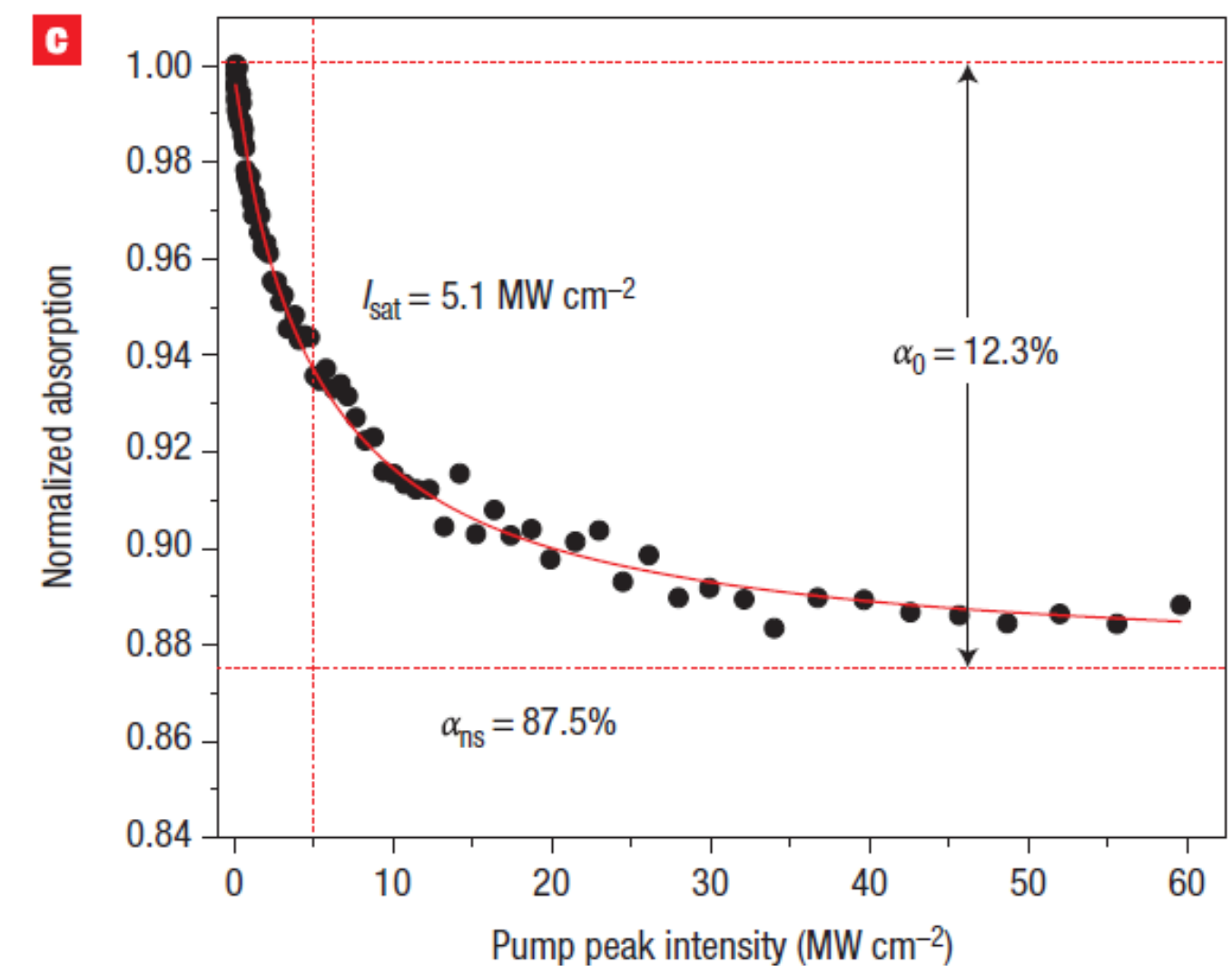
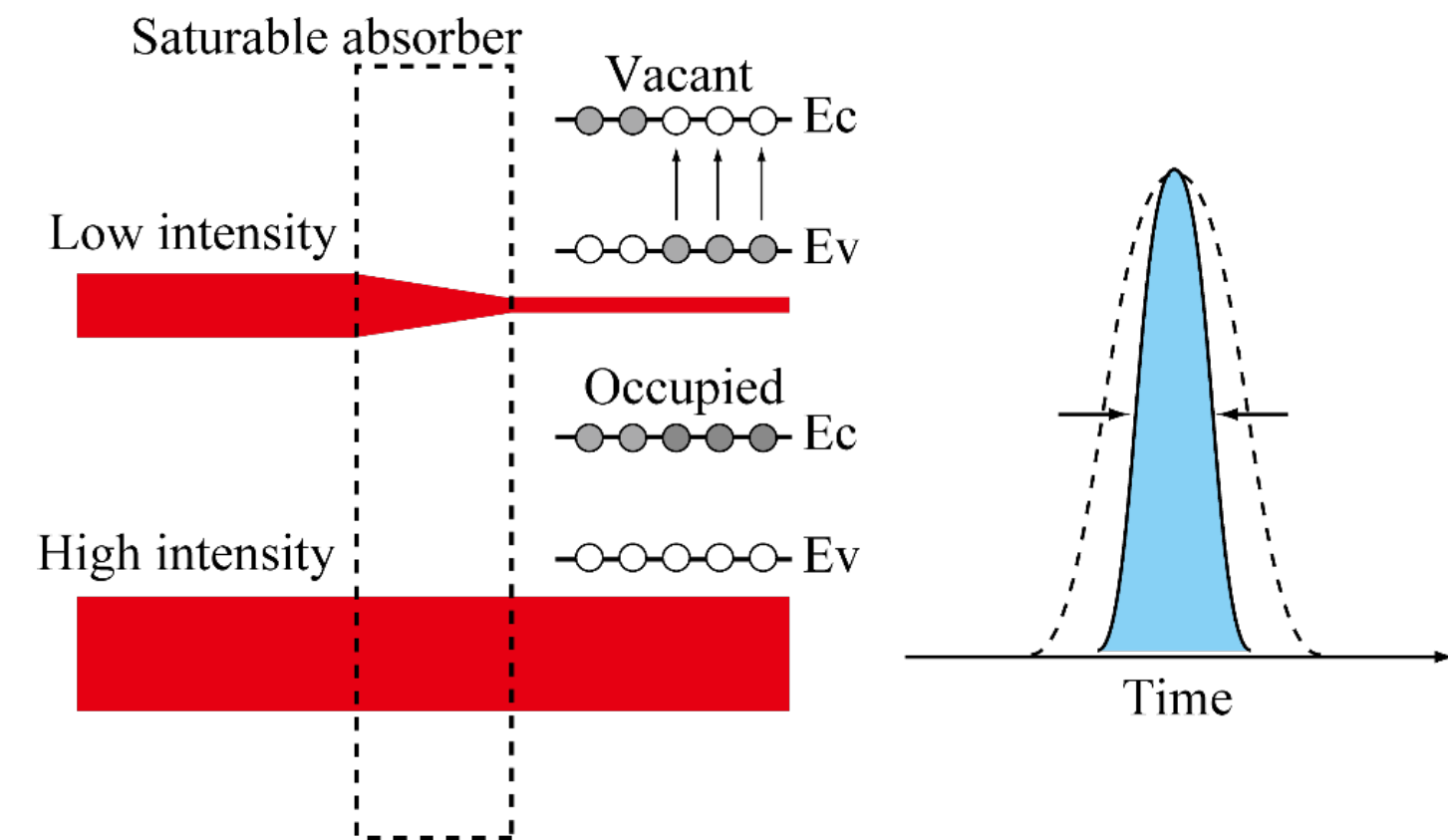
lasing at 1550 nm      saturable absorber (CNT)

Realizing this system with microcavity

cavity length : 13.3 m → 200 μm

$f_{\text{rep}}$  : 15 MHz → 1000 GHz

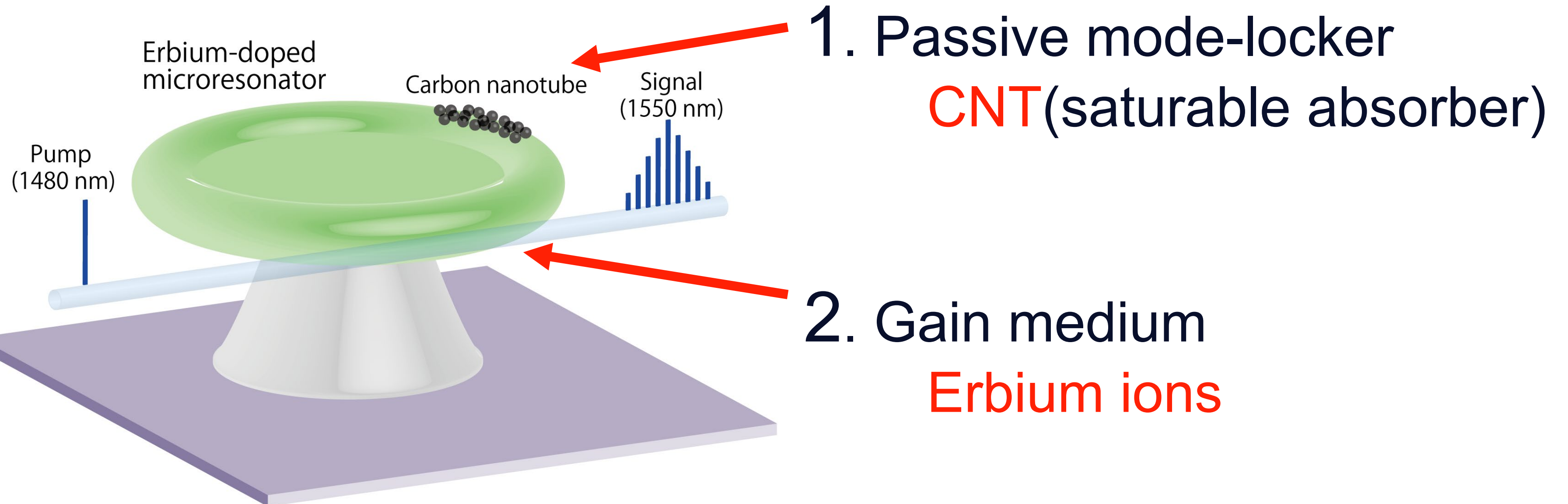
## Saturable absorption



# Objective:

## Mode-locked laser with microresonator

- high repetition rate ( $> \text{GHz}$ )
- small footprint
- on-chip integrability

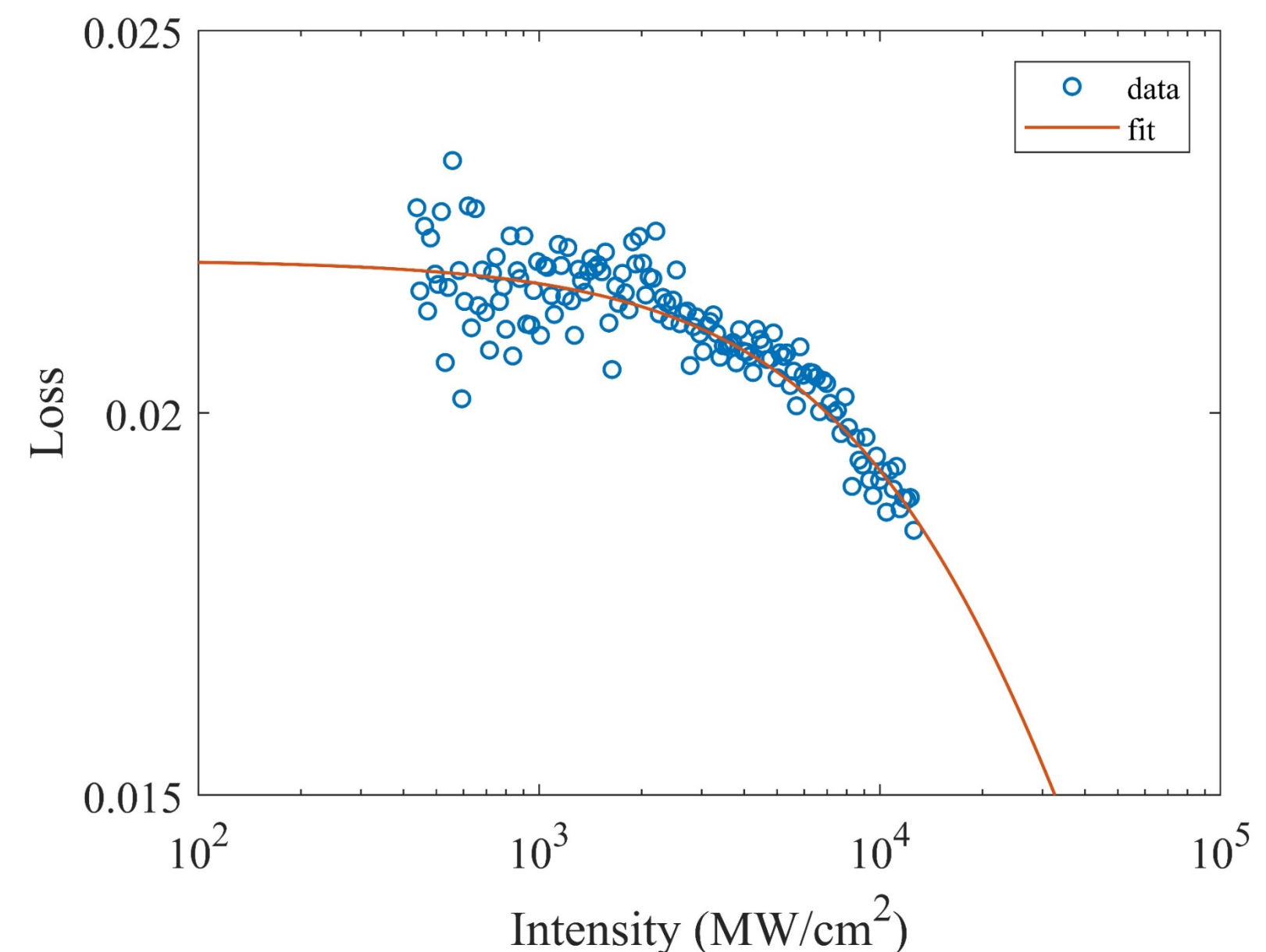
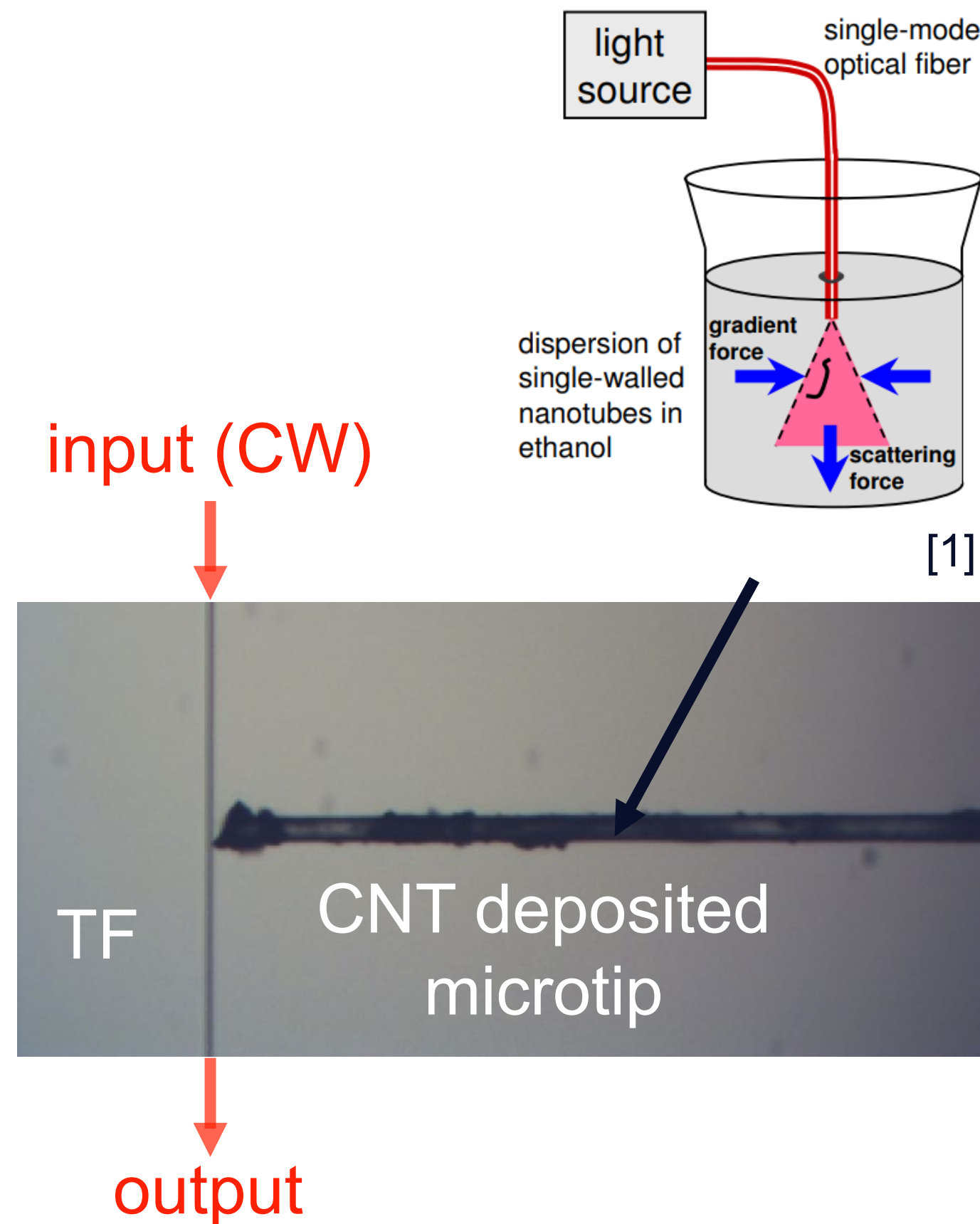






# Saturable absorption of CNT

## Optical deposition on fiber microtip

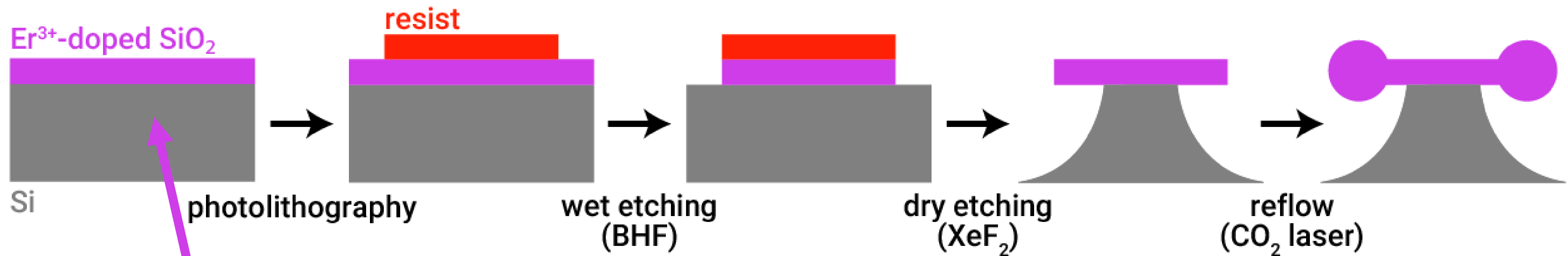


- By using optical deposited fiber tip, saturable absorption was observed
- By changing the gap distance between microtip and tapered fiber, the absorption can be controlled.

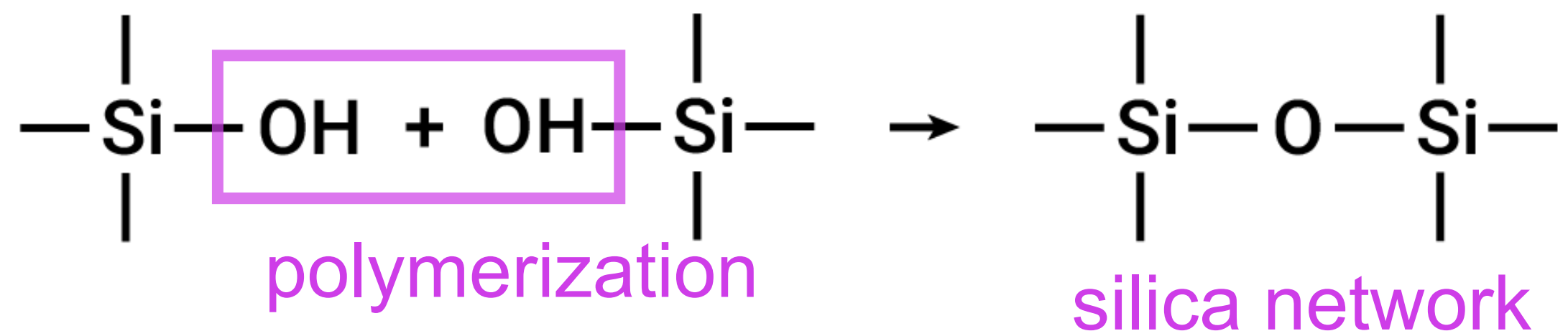
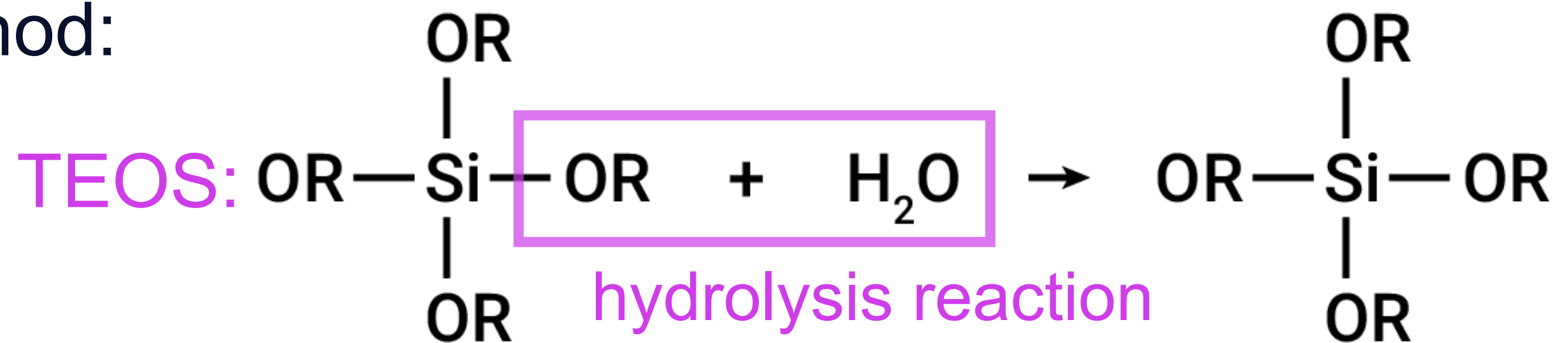


# Er-doped microresonator: Process flow

Fabrication flow of microtoroid by sol-gel method (cross-section).

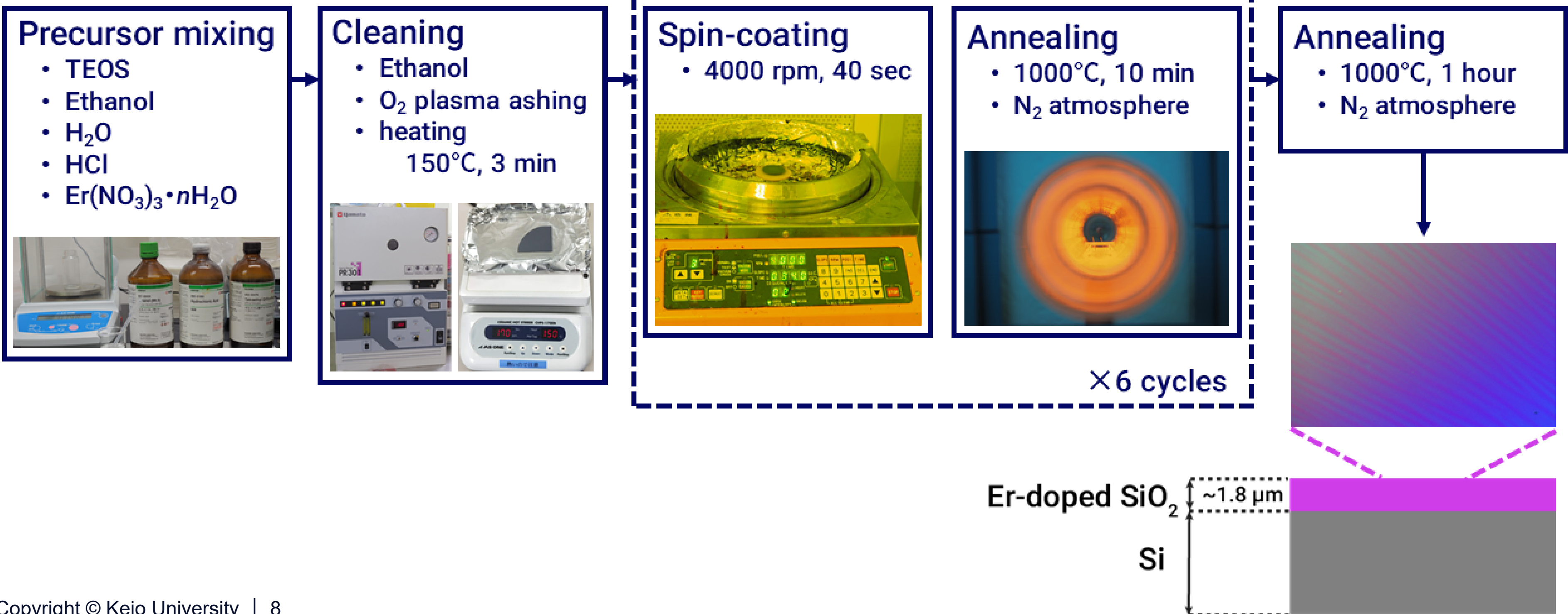
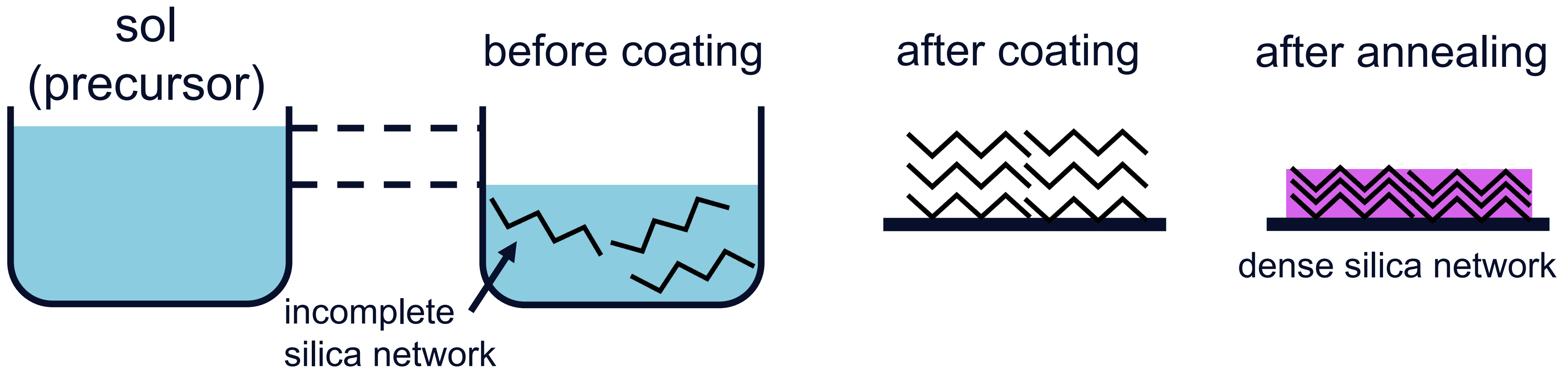


sol-gel method:





# Er-doped microresonator: Process flow



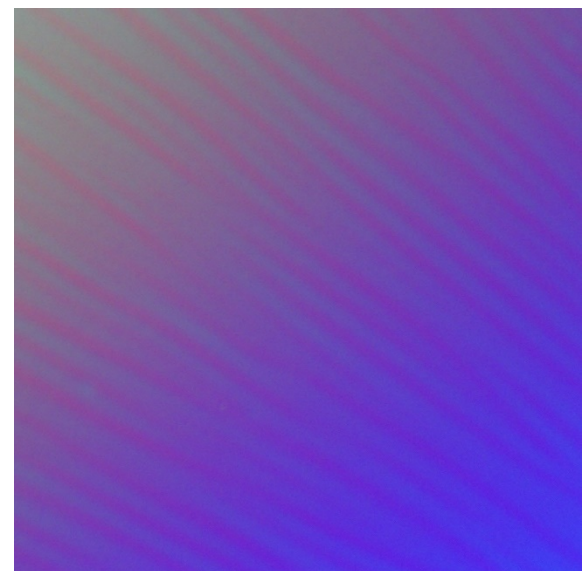




# Er-doped microresonator: Fabrication result

The thickness of sol-gel film is  $\sim 1.8 \mu\text{m}$  with 6 layers ( $\sim 300 \text{ nm/layer}$ ).

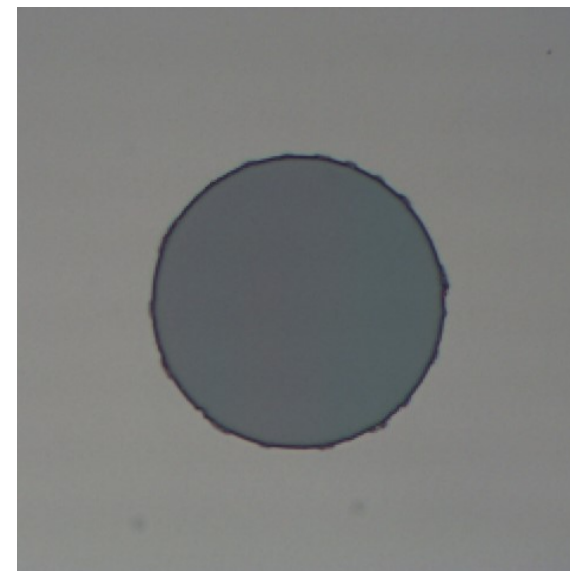
forming sol-gel film



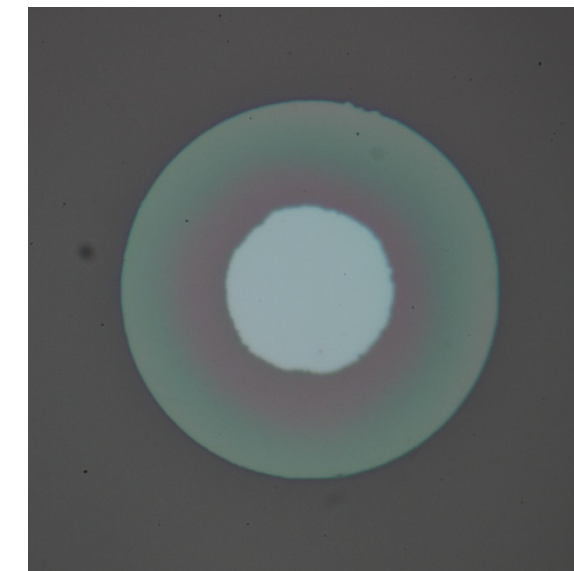
forming pattern



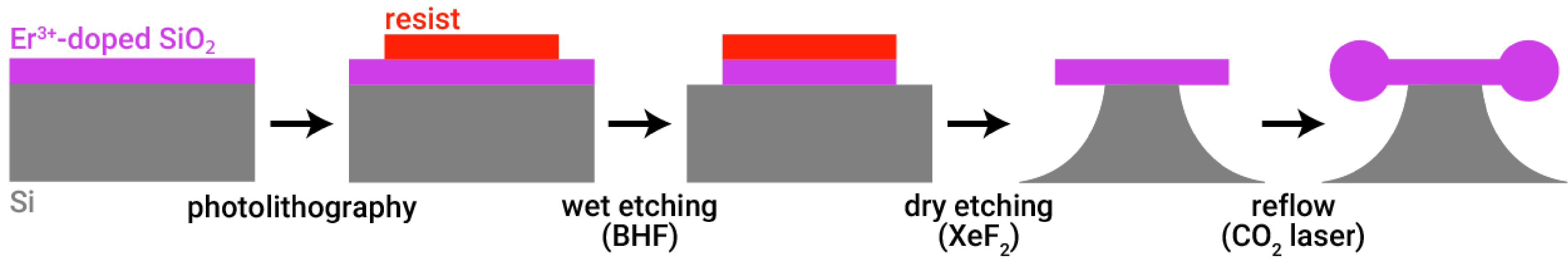
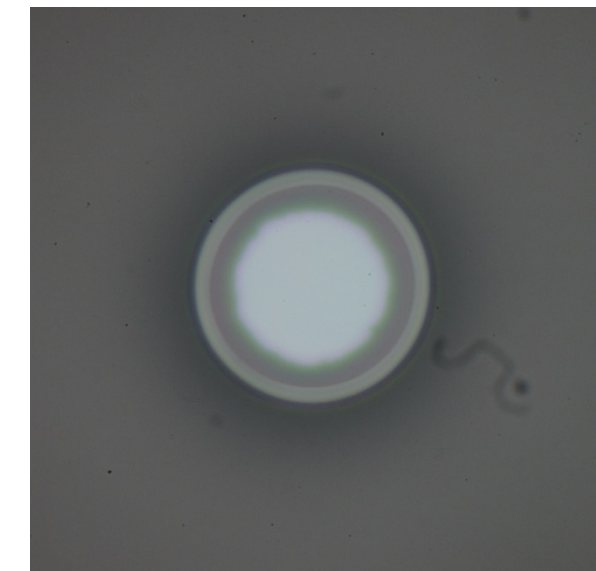
etching of silica layer



undercutting silicon pillar

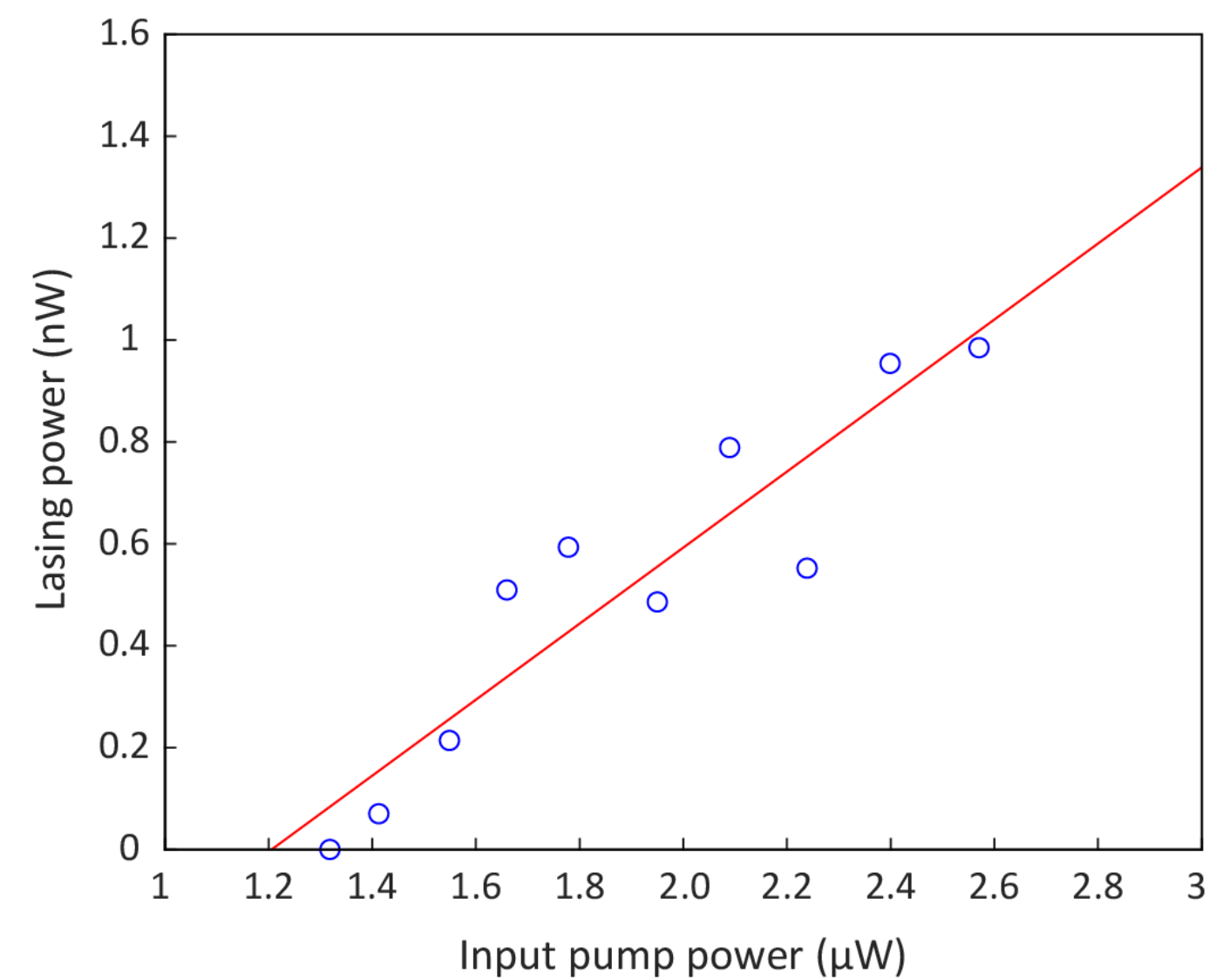
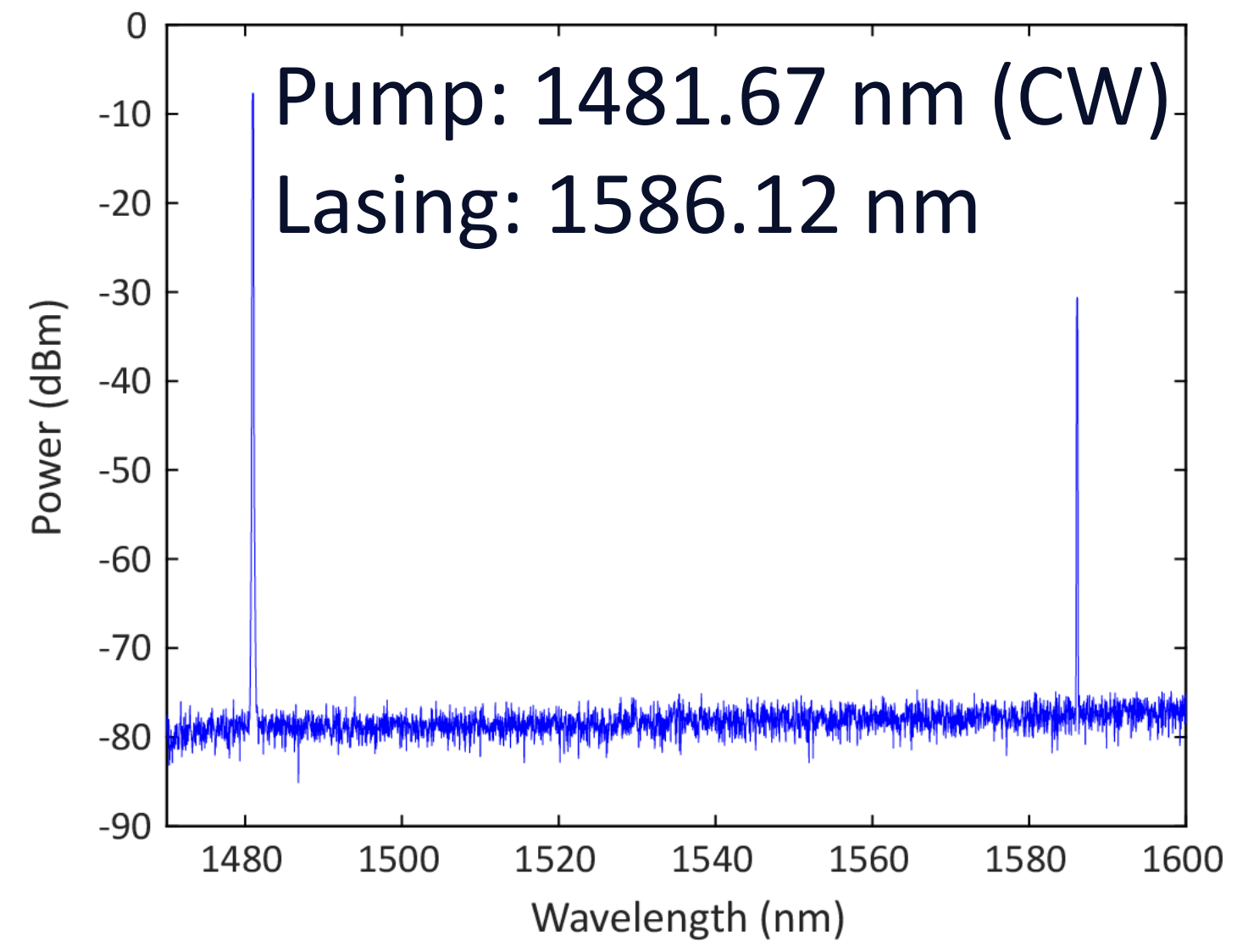
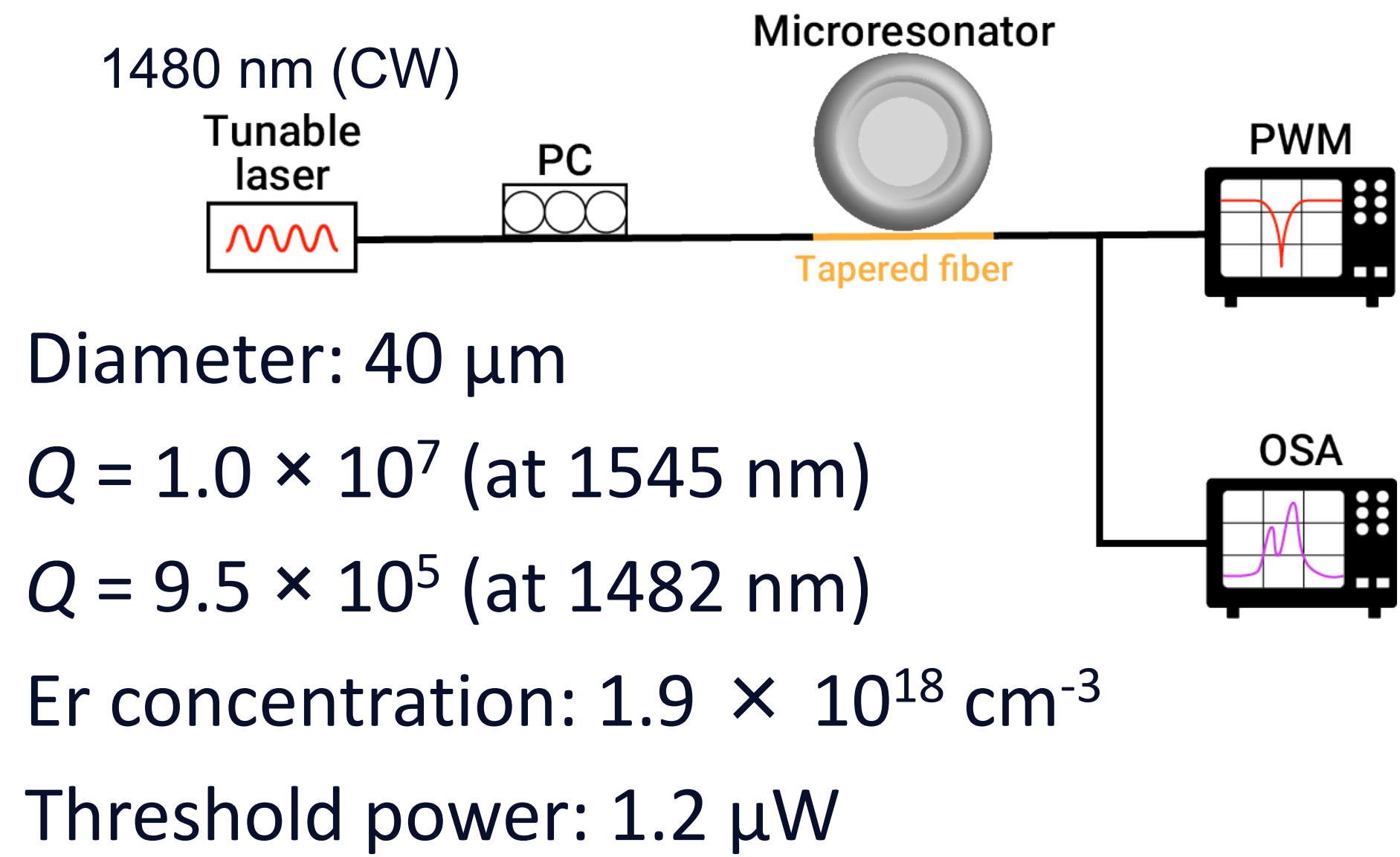
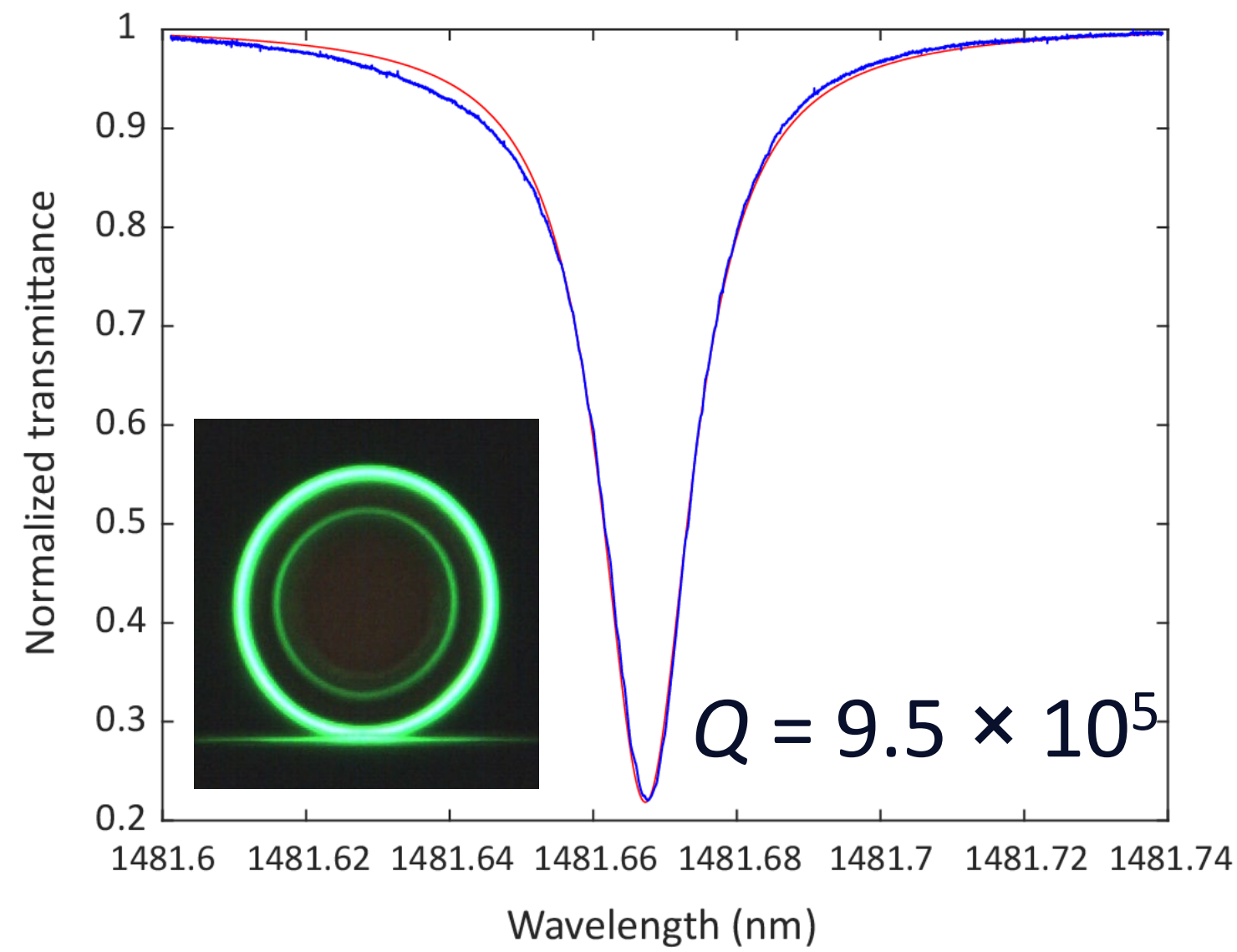


forming toroidal rim





# Er-doped microresonator: Measurement



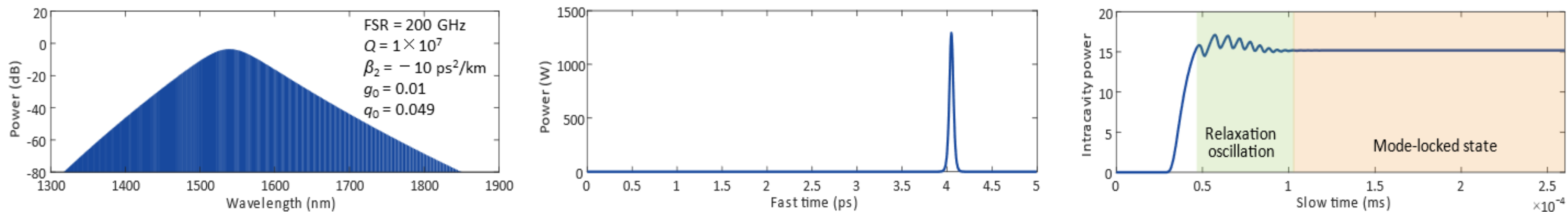




# Next step

Model: Nonlinear Schrödinger equation

$$t_R \frac{\partial E(t, \tau)}{\partial t} = \left[ -\frac{\alpha_{\text{tot}}}{2} - \frac{iL}{2} \beta_2 \frac{\partial^2}{\partial \tau^2} + iL\gamma |E|^2 + g(t) + \frac{g(t)}{\Omega_g^2} \frac{\partial^2}{\partial \tau^2} - q(t, \tau) \right] E$$



A gain of  $g_0 = 0.01$  (/ roundtrip) is needed to achieve pulse operation.

1. Increasing cavity length
  - Large size toroidal cavity
2. Changing dopant
  - Erbium / Ytterbium co-doping
  - Erbium / Aluminum co-doping



# Summary

## Objective:

On-chip mode-locked laser with CNT and Er-doped microresonator

## Achievement:

- Saturable absorption of CNT
  - SA is obtained by using microtip
- Er-doped microresonator
  - Fabrication of Er-doped microtoroid
  - Lasing at  $\sim 1580$  nm

## Future plan:

- Fabricating a higher gain microresonator
- Integration of CNT and Er-doped microtoroid



# Thank you.

## Acknowledgement:

- Japan Society for the Promotion of Science (JSPS) KAKENHI under Grant Number JP19H00873 and Grantin-Aid for JSPS Fellow.
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